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(54) **BUMP STRUCTURE HAVING A SIDE RECESS AND SEMICONDUCTOR STRUCTURE INCLUDING THE SAME**

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CPC ..... **H01L 24/13** (2013.01); **H01L 24/14** (2013.01); **H01L 24/16** (2013.01); **H01L 24/81** (2013.01); **H01L 2224/0401** (2013.01); **H01L 2224/05572** (2013.01); **H01L 2224/05599** (2013.01); **H01L 2224/10145** (2013.01); **H01L 2224/131** (2013.01); **H01L 2224/13011** (2013.01); **H01L 2224/13015** (2013.01); **H01L**

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(58) **Field of Classification Search**

None

See application file for complete search history.

(56) **References Cited**

**U.S. PATENT DOCUMENTS**

5,477,086	A	12/1995	Rostoker et al.
5,569,964	A	10/1996	Ikebe
5,767,580	A	6/1998	Rostoker
6,037,667	A	3/2000	Hembree et al.
6,205,660	B1	3/2001	Fjelstad et al.

(Continued)

**OTHER PUBLICATIONS**

Office Action dated Feb. 14, 2014 from corresponding application No. TW 101112185.

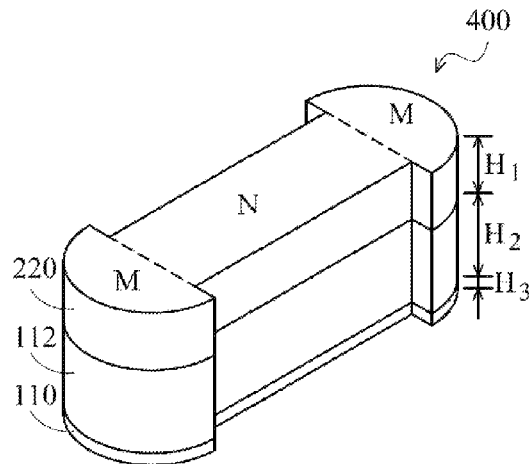
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(57) **ABSTRACT**

A bump structure includes a first end; and a second end opposite the first end. The bump structure further includes a side connected between the first end and the second end, wherein the side comprises a recess for a reflowed solder material to fill, and the recess defines a first surface adjacent to the first end and a second surface adjacent to the second end.

**20 Claims, 16 Drawing Sheets**



(56)

**References Cited**

U.S. PATENT DOCUMENTS

6,562,545	B1	5/2003	Hembree et al.
7,057,292	B1	6/2006	Elenius et al.
7,271,483	B2	9/2007	Lin et al.
8,288,871	B1	10/2012	Shieh et al.
8,299,367	B2	10/2012	Ni et al.
8,970,033	B2	3/2015	Chen et al.
2003/0052156	A1	3/2003	Kim et al.

2008/0073783	A1	3/2008	Matsushima et al.
2008/0088016	A1	4/2008	Ho et al.
2009/0243006	A1 *	10/2009	Takahashi et al. .... 257/415
2010/0044416	A1 *	2/2010	Ogawa ..... 228/164
2010/0187688	A1	7/2010	Hochstenbach
2010/0193944	A1	8/2010	Castro et al.
2010/0326715	A1 *	12/2010	Lee et al. .... 174/260
2011/0248399	A1	10/2011	Pendse
2011/0260321	A1	10/2011	Pendse
2012/0032325	A1	2/2012	Miyata et al.

\* cited by examiner

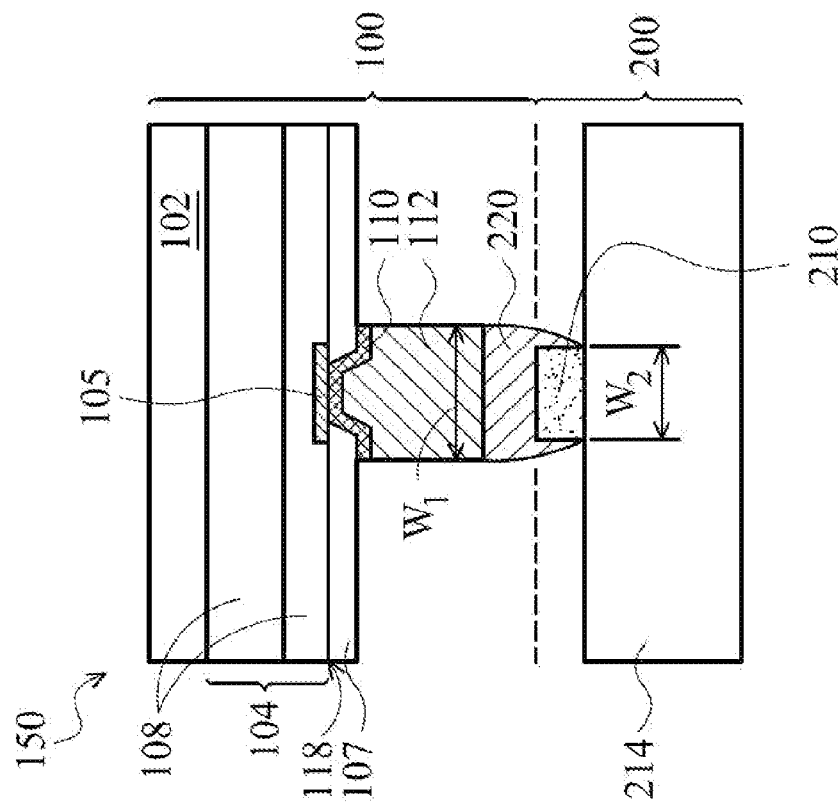


Fig. 13

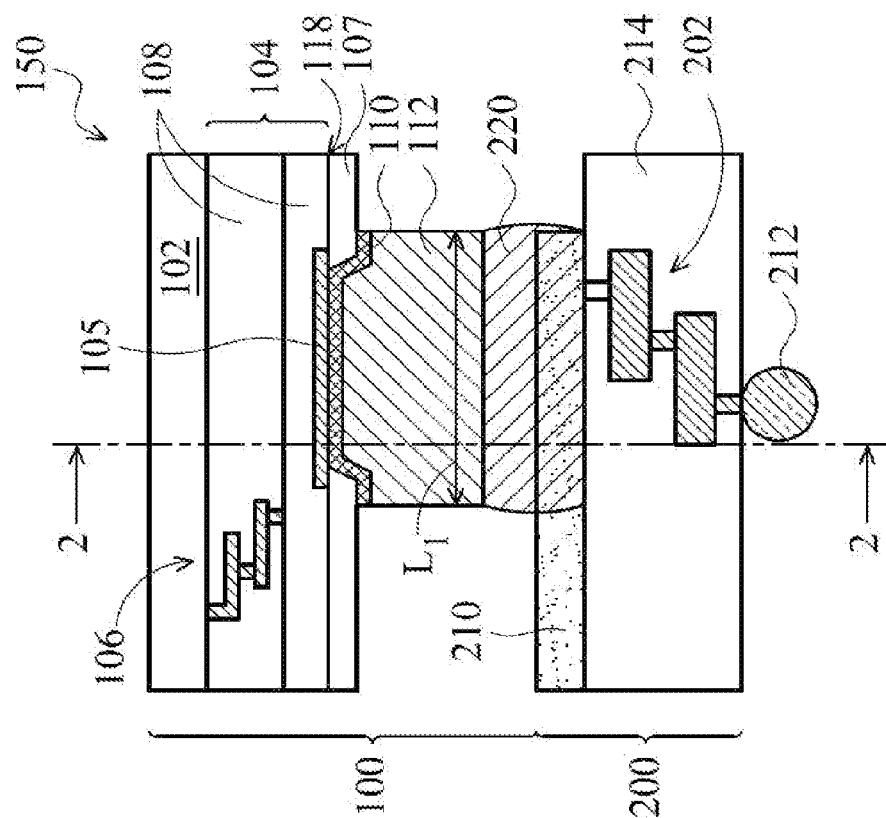


Fig. 1A

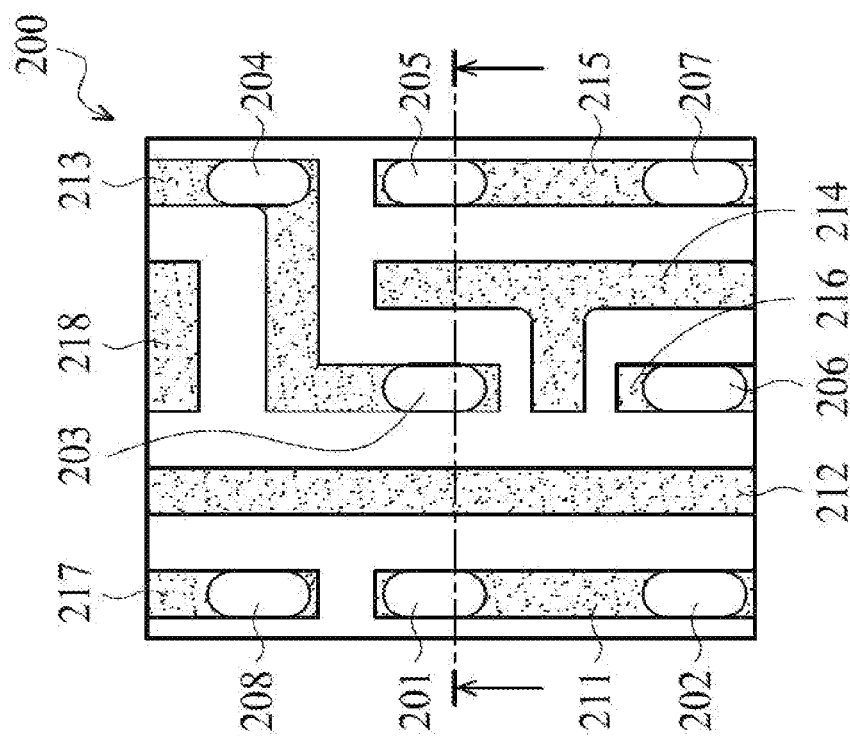


Fig. 2A

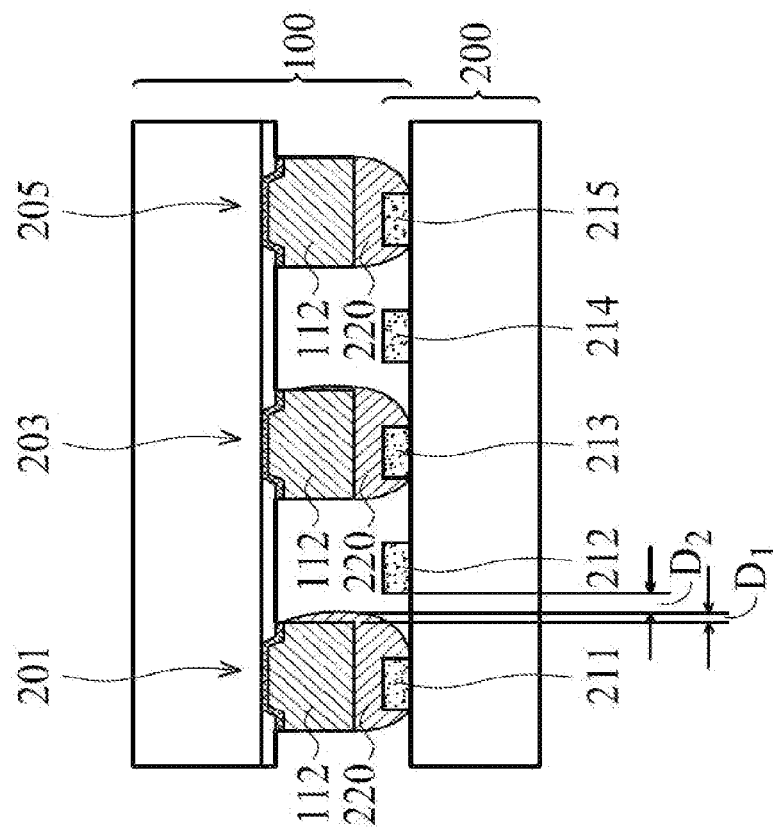


Fig. 2B

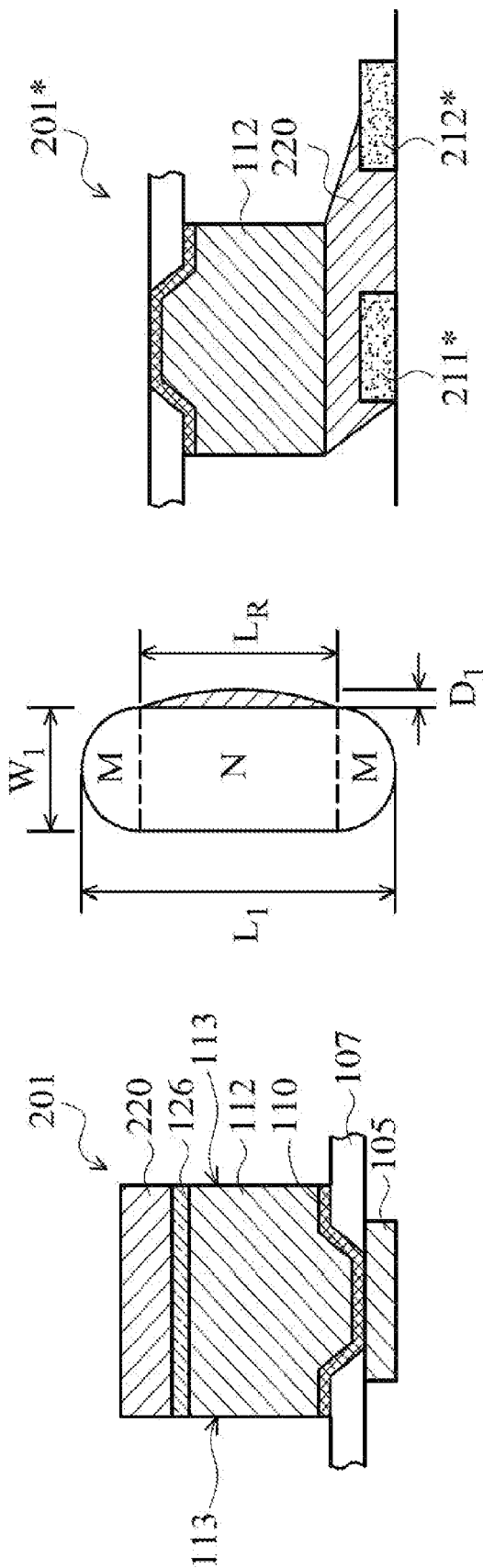


Fig. 3A

Fig. 3B

Fig. 3C

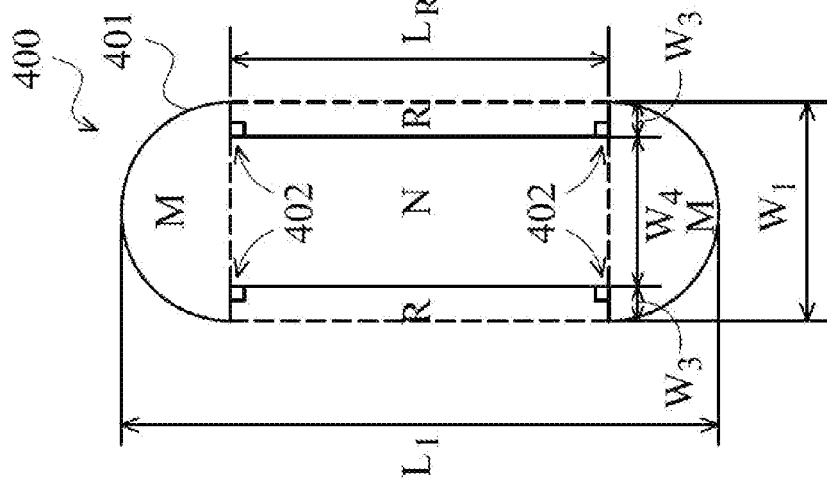


Fig. 4A

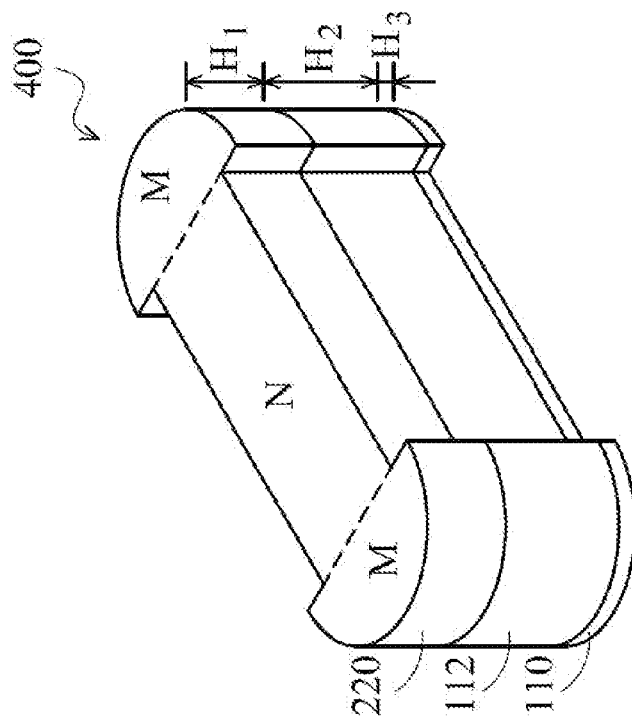


Fig. 4B

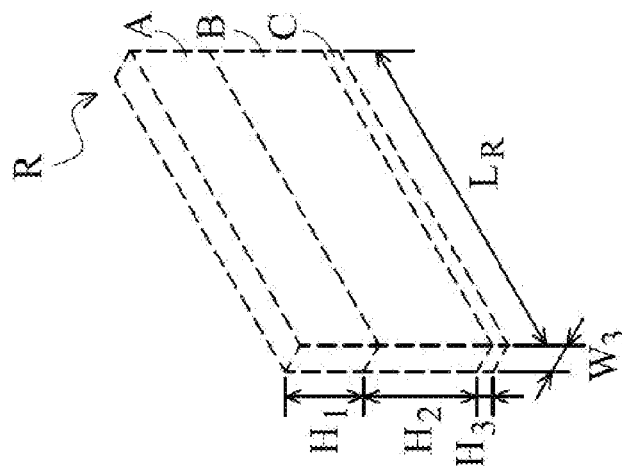


Fig. 4C

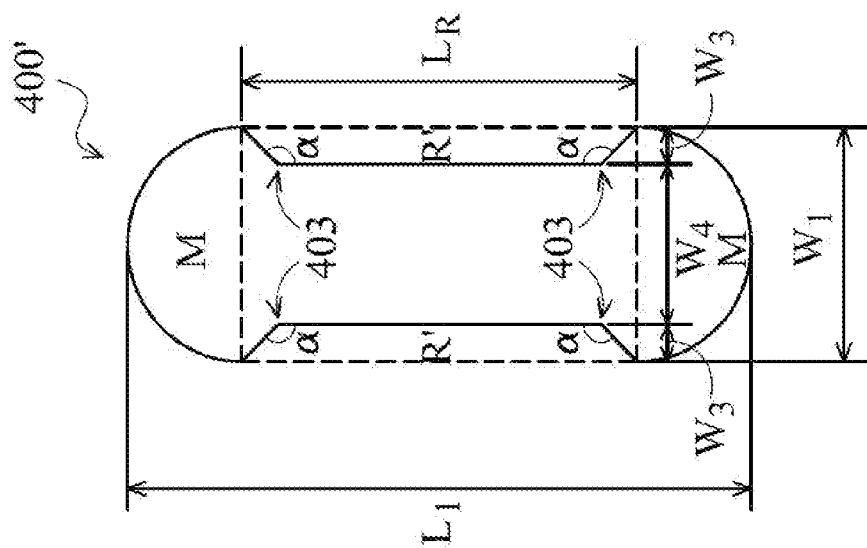


Fig. 4D

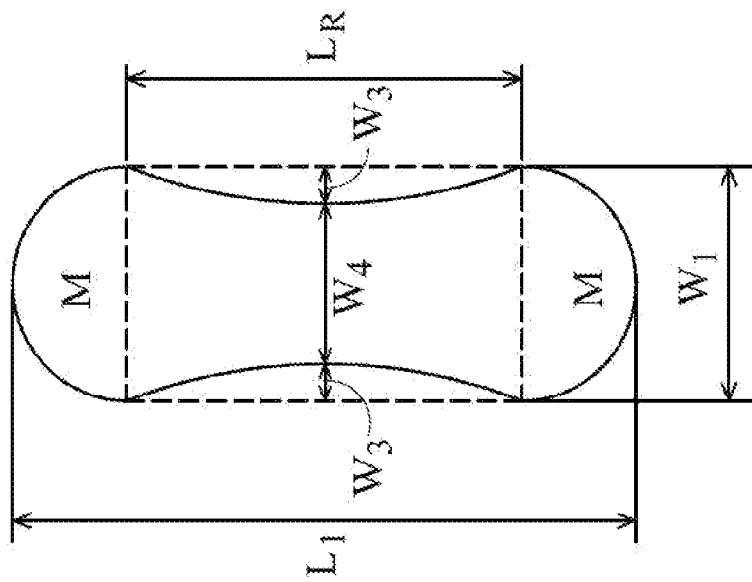


Fig. 4E

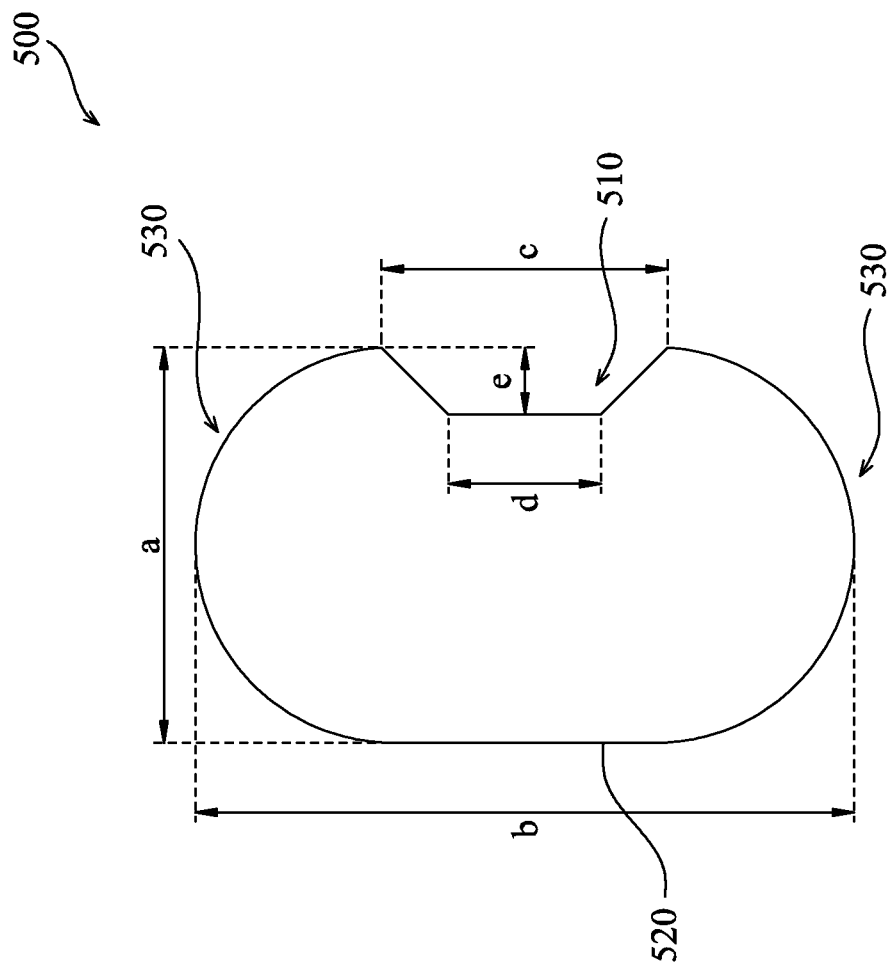


Fig. 5A



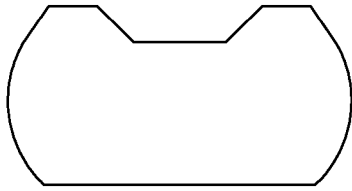


Fig. 5D

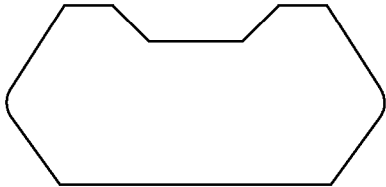


Fig. 5C

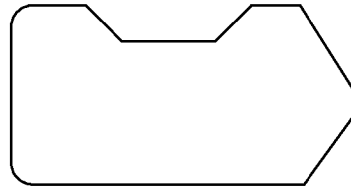


Fig. 5F

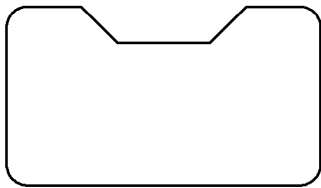


Fig. 5B

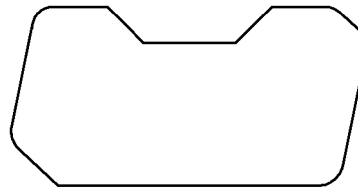


Fig. 5E

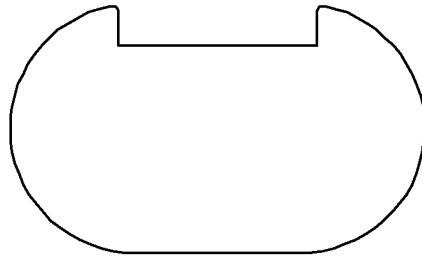


Fig. 5I

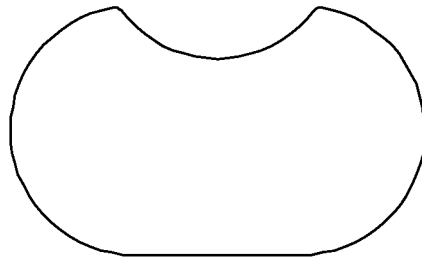


Fig. 5H

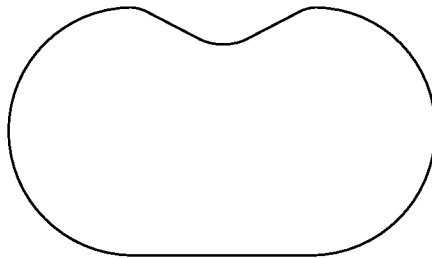


Fig. 5G

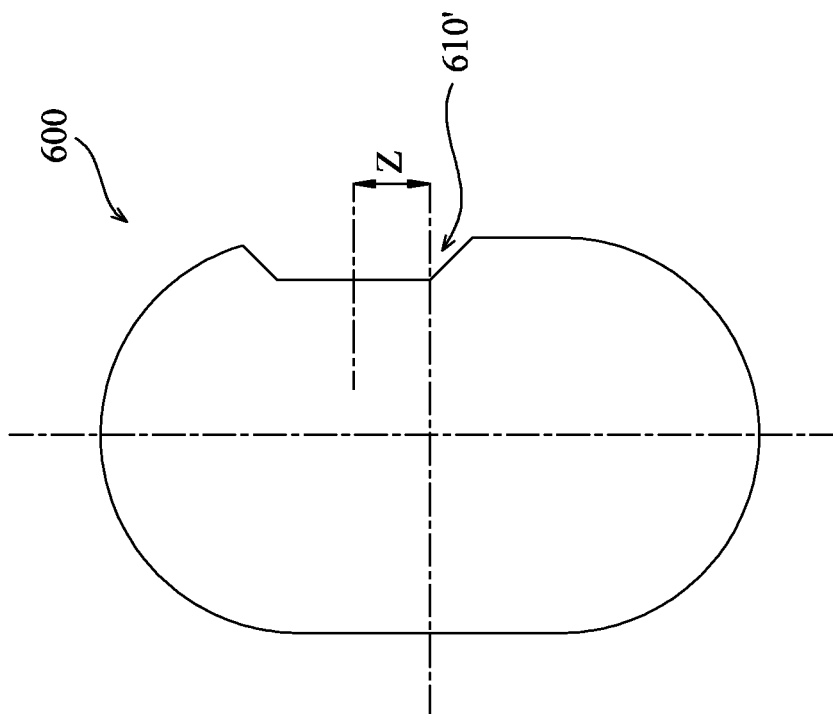


Fig. 6

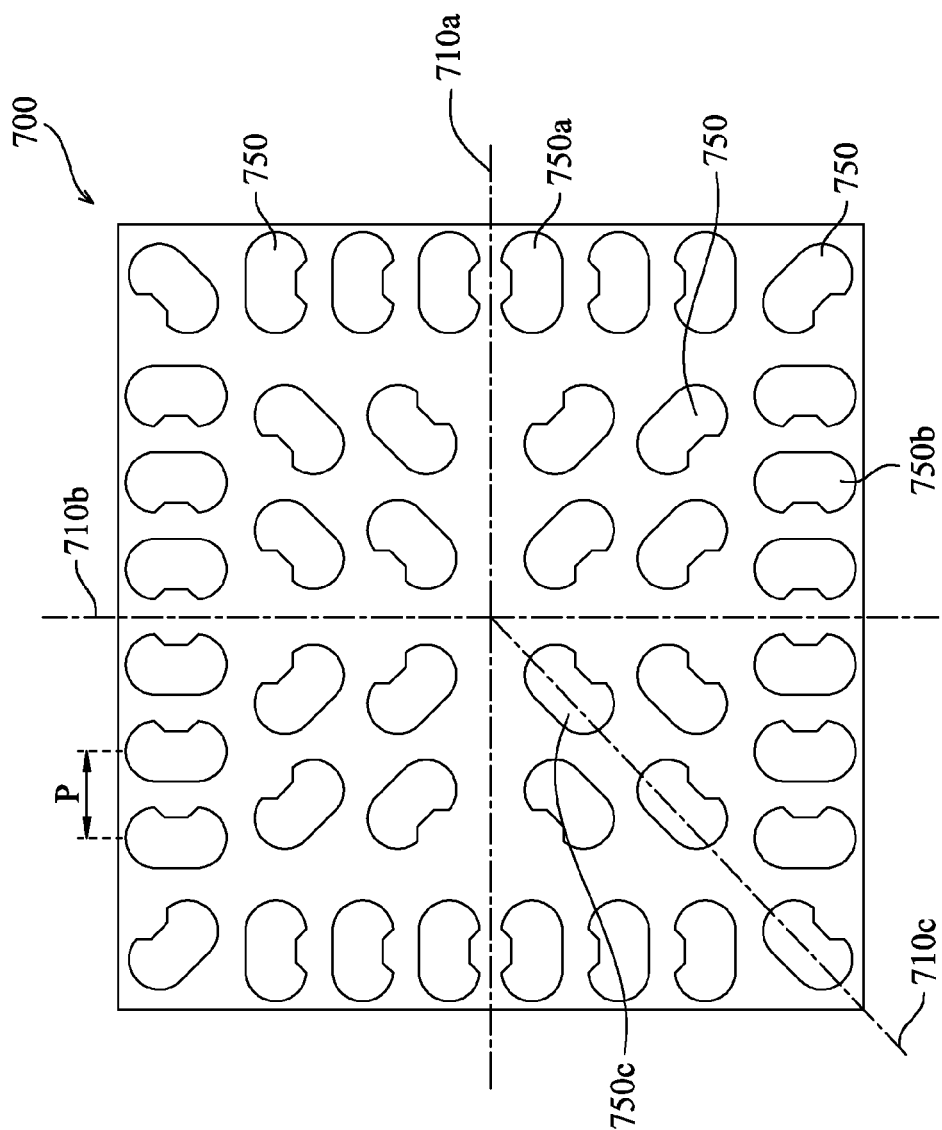


Fig. 7

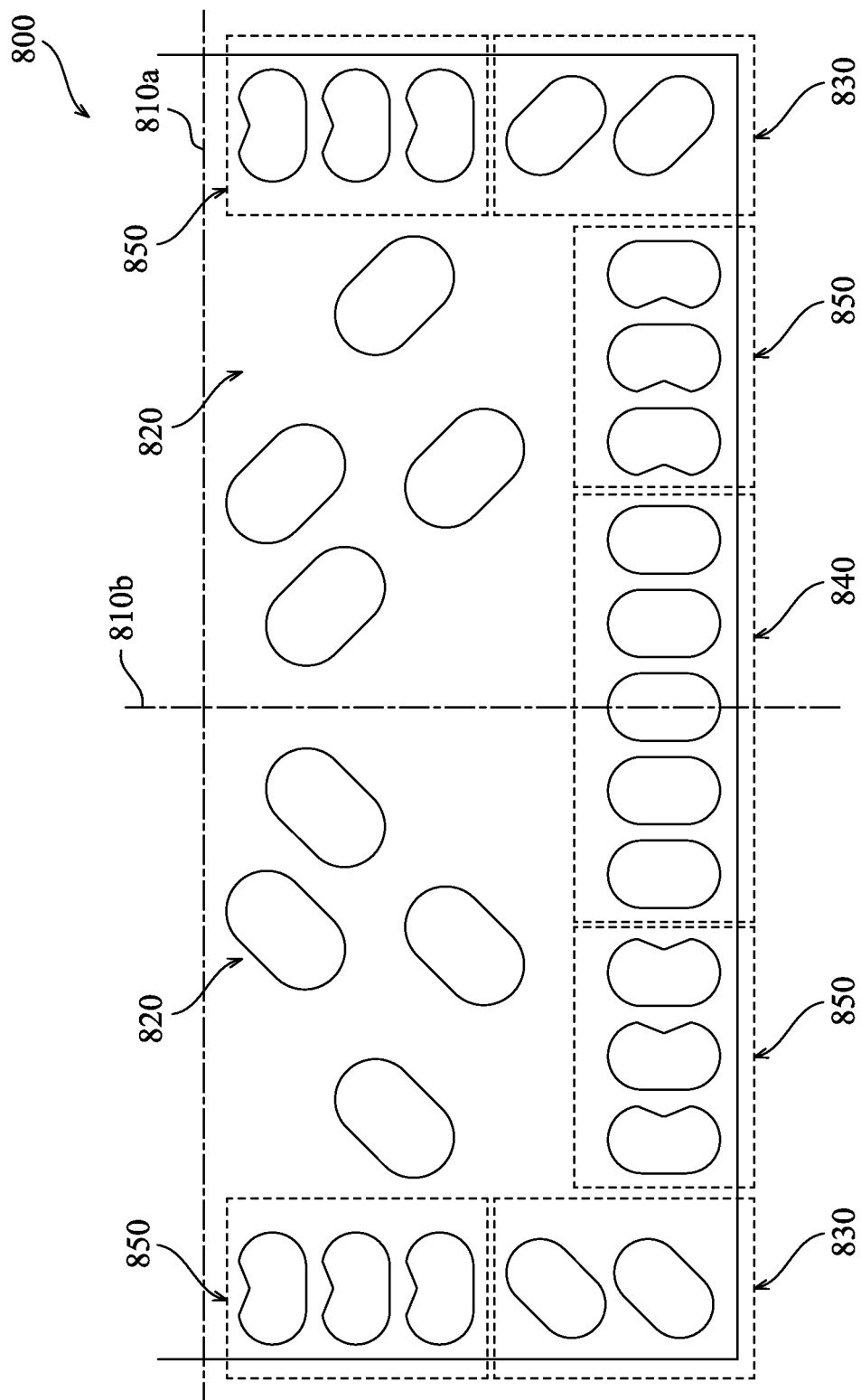


Fig. 8

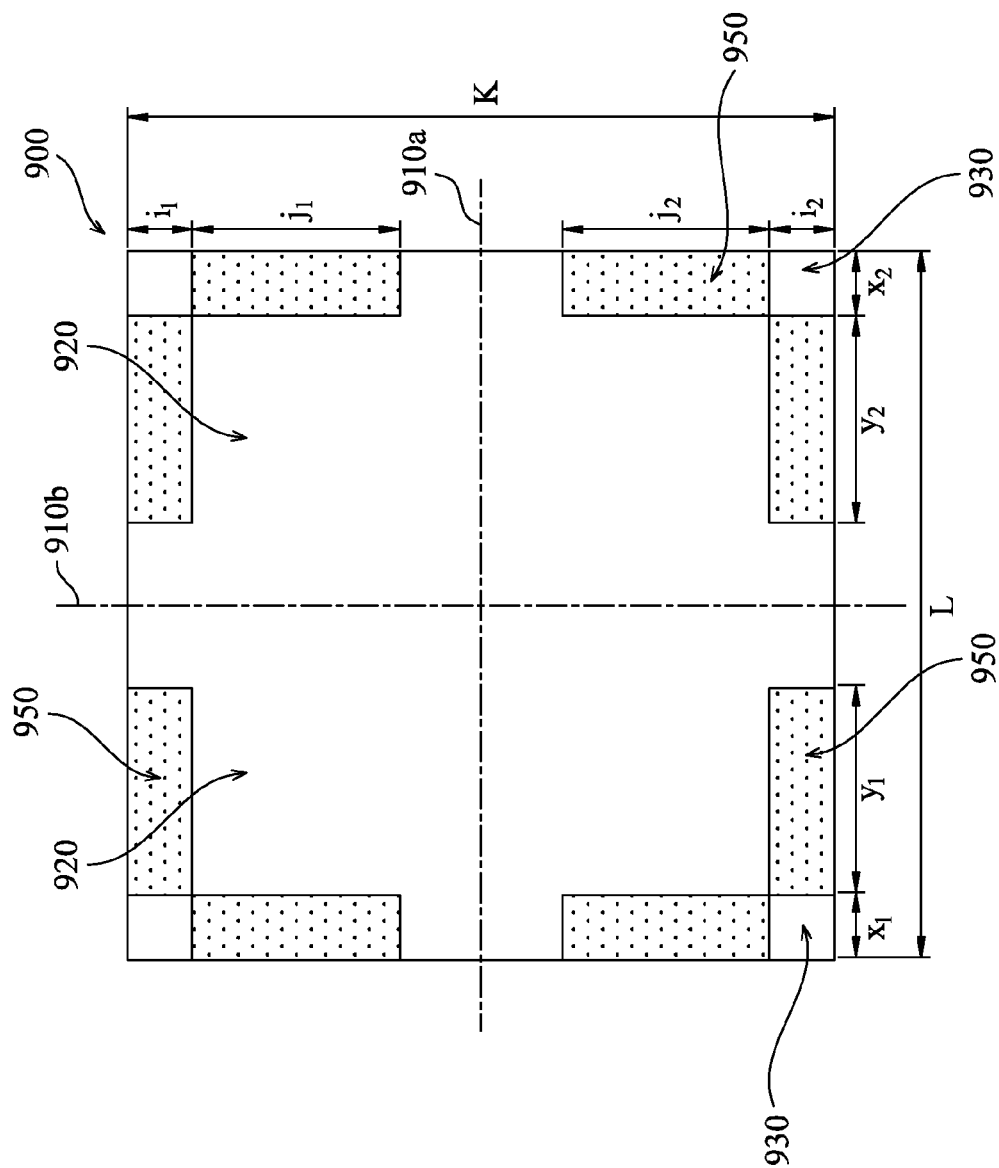


Fig. 9

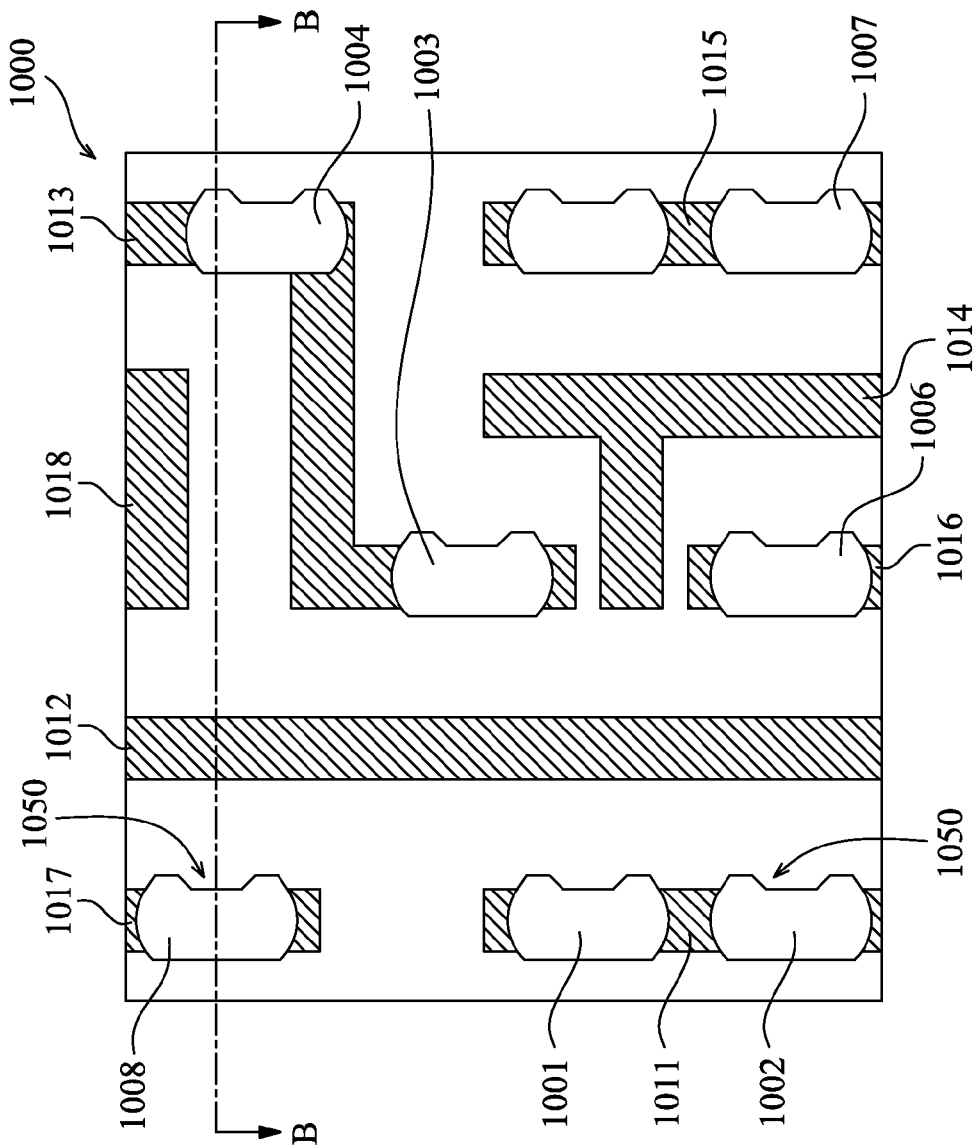


Fig. 10A

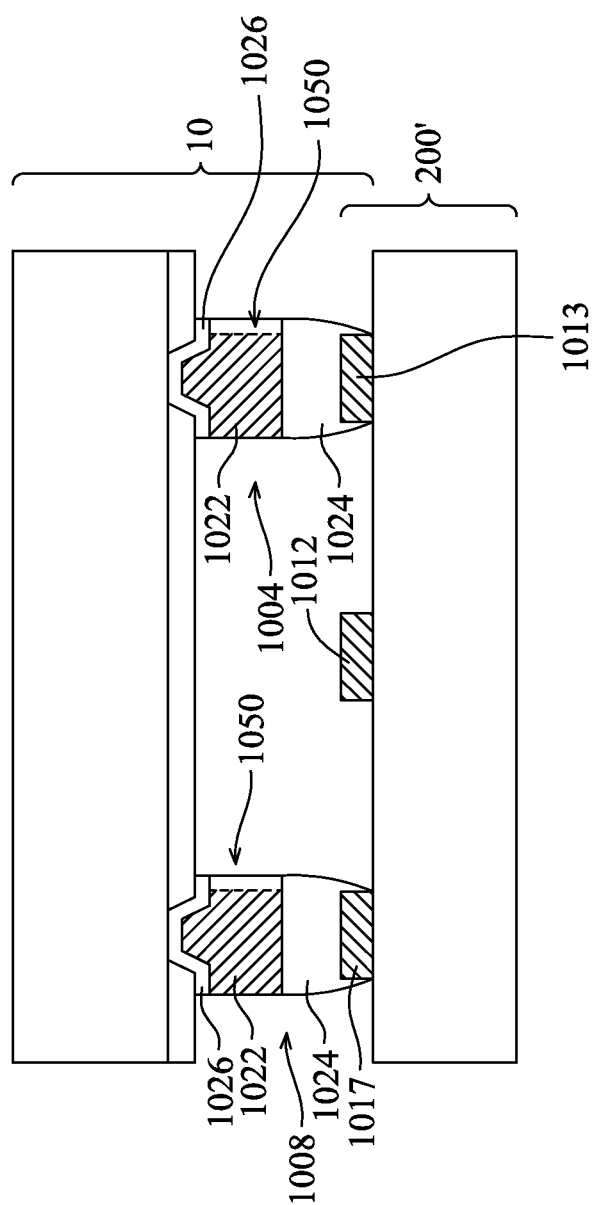


Fig. 10B



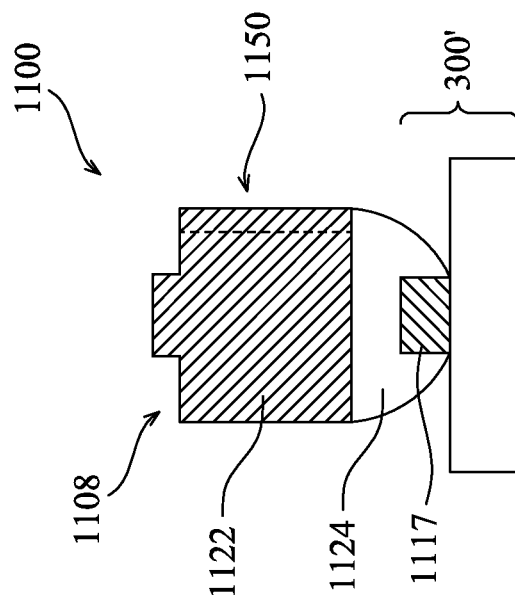


Fig. 11A

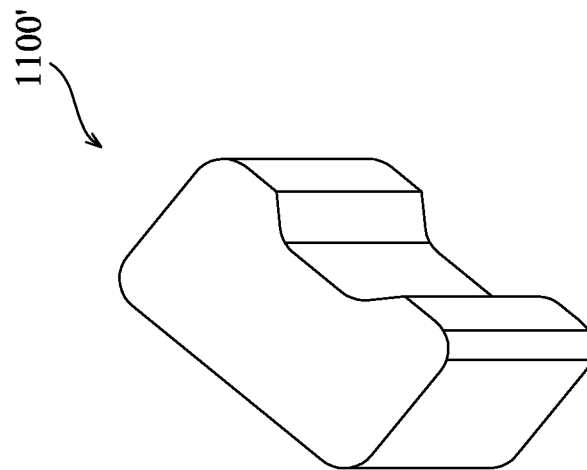


Fig. 11B

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# BUMP STRUCTURE HAVING A SIDE RECESS AND SEMICONDUCTOR STRUCTURE INCLUDING THE SAME

## PRIORITY CLAIM

The present application is a continuation of U.S. application Ser. No. 14/507,189, filed Oct. 6, 2014, which is a continuation-in-part of U.S. application Ser. No. 13/192,302, filed Jul. 27, 2011, now U.S. Pat. No. 8,853,853, issued Oct. 7, 2014, which are incorporated herein by reference in their entireties.

## RELATED APPLICATIONS

U.S. Pat. No. 8,853,853 is related to U.S. application Ser. No. 13/035,586, filed Feb. 25, 2011 and the present application is also related to U.S. application Ser. No. 13/095,185, filed Apr. 27, 2011, each of which are incorporated herein by reference in their entireties.

## BACKGROUND

Bump-on-Trace (BOT) structures have been used in flip chip packages, wherein metal bumps are bonded onto narrow metal traces in package substrates directly, rather than bonded onto metal pads that have greater widths than the respective connecting metal traces. The BOT structures require smaller chip areas, and the manufacturing cost of the BOT structures is relatively low. However, there are technical challenges related to BOT structures.

## BRIEF DESCRIPTION OF THE DRAWINGS

For a more complete understanding of the embodiments, and the advantages thereof, reference is now made to the following descriptions taken in conjunction with the accompanying drawings, in which:

FIGS. 1A and 1B illustrate cross-sectional views of a package structure in accordance with an embodiment.

FIGS. 2A and 2B illustrate top and cross-sectional views of a bump-on-trace (BOT) region, in accordance with some embodiments.

FIGS. 3A and 3B illustrate cross-sectional and top views of a metal bump, in accordance with some embodiments.

FIG. 3C illustrates protruding solder shorting with a neighboring metal trace, in accordance with some embodiments.

FIGS. 4A-4E illustrate various embodiments of metal bumps with recess regions to reduce solder protrusion, in accordance with some embodiments.

FIGS. 5A-5I are top views of a bump structure having a single side recess in accordance with some embodiments.

FIG. 6 is a top view of a bump structure having a single side recess in accordance with some embodiments.

FIG. 7 is a top view of an array of bump structures having a single side recess on a die in accordance with some embodiments.

FIG. 8 is a top view of a portion of an array of bump structures having a single side recess on a die in accordance with some embodiments.

FIG. 9 is a top view of a die having bump structures having a single side recess in accordance with some embodiments.

FIG. 10A is a top view of a BOT region in accordance with some embodiments.

FIG. 10B is a cross-sectional view of a BOT region in accordance with some embodiments.

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FIG. 11A is a cross-sectional view of a BOT region in accordance with some embodiments.

FIG. 11B is a perspective view of a bump structure having a single side recess in accordance with some embodiments.

## DETAILED DESCRIPTION OF ILLUSTRATIVE EMBODIMENTS

The making and using of the embodiments of the disclosure are discussed in detail below. It should be appreciated, however, that the embodiments provide many applicable inventive concepts that can be embodied in a wide variety of specific contexts. The specific embodiments discussed are merely illustrative, and do not limit the scope of the disclosure.

Cross-sectional views of a package structure comprising a Bump-on-Trace (BOT) structure **150** is provided in FIGS. 1A and 1B, in accordance with some embodiments. The package structure **150** includes work piece **100** bonded to work piece **200**. Work piece **100** may be a device die that includes active devices such as transistors (not shown) therein, although work piece **100** may also be an interposer that does not have active devices therein. In an embodiment wherein work piece **100** is a device die, substrate **102** may be a semiconductor substrate such as a silicon substrate, although it may include other semiconductor materials. Interconnect structure **104**, which includes metal lines and vias **106** formed therein and connected to the semiconductor devices, is formed on substrate **102**. Metal lines and vias **106** may be formed of copper or copper alloys, and may be formed using damascene processes. Interconnect structure **104** may include a commonly known inter-layer dielectric (ILD, not shown) and inter-metal dielectrics (IMDs) **108**. IMDs **108** may comprise low-k dielectric materials, and may have dielectric constants (k values) lower than about 3.0. The low-k dielectric materials may also be extreme low-k dielectric materials having k values lower than about 2.5.

Work piece **100** may further include under-bump metal-lurgy (UBM) layer **110** and a copper post (or pillar) **112** on UBM layer **110**. Throughout the description, the copper post **112** is also referred to as a copper-containing bump or metal bump. Although copper post **112** is used as an example in the description here and below, other types of metal bumps, such as solder bumps, may also be used in place of copper post **112**. The UBM layer **110** is disposed on a metal pad **105**, which is part of interconnect structure **104**. Between the interconnect structure **104** and the UBM layer **110** not contacting the metal pad **105**, there is a passivation layer **107**. In some embodiments, the passivation layer **107** is made of polyimide.

Work piece **200** may be a package substrate, although it may be other package components such as interposers, for example. Work piece **200** may include metal lines and vias **202** connecting metal features on opposite sides of work piece **200**. In an embodiment, metal trace(s) **210** on the top side of work piece **200** is electrically connected to ball grid array (BGA) balls **212** on the bottom side of work pieces **200** through metal lines and vias **202**. Metal lines and vias **202** may be formed in dielectric layers **214**, although they may also be formed in a semiconductor layer (such as a silicon layer, not shown) and in the dielectric layers that are formed on the semiconductor layer.

Metal trace **210** is formed over a top dielectric layer in dielectric layers **214**. Metal trace **210** may be formed of substantially pure copper, aluminum copper, or other metallic materials such as tungsten, nickel, palladium, gold, and/or alloys thereof. FIG. 1A shows that the copper post (or metal bump) **112** has a length of  $L_1$ , in accordance with some

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embodiments. Work pieces **100** and **200** are bonded to each other through solder layer **220**, which may be formed of a lead-free solder, a eutectic solder, or the like. Solder layer **220** is bonded to, and contacts, the top surfaces of metal trace **210** and copper post **112**.

FIG. 1B illustrates a cross-sectional view of the package structure **150** shown in FIG. 1A, wherein the cross-sectional view is obtained from the plane crossing line 2-2 in FIG. 1A. As shown in FIG. 1B, solder layer **220** may also contact the sidewalls of metal trace **210** after solder reflow. The reflowed solder layer **220** may also move along surfaces **113** of copper post **112** and cover portions or all of surfaces **113** (not shown). In some embodiments, there is a capping layer between copper post **112** and solder layer **220**. The capping layer could be used to prevent the formation of inter-metallic compound(s) from copper and solder. In some embodiments, the capping layer includes nickel (Ni). Exemplary details of materials and processes used in forming work piece **100** are described in U.S. application Ser. No. 13/095,185, entitled "REDUCED-STRESS BUMP-ON-TRACE (BOT) STRUCTURES," filed on Apr. 27, 2011, which is incorporated herein by reference in its entirety.

After the bonding of work pieces **100** and **200**, a mold underfill (MUF) (not shown) may be filled into the space between work pieces **100** and **200**, in accordance with some embodiments. Accordingly, a MUF may also be filled into the space between neighboring metal traces **210**. Alternatively, no MUF is filled, while air fills the space between work pieces **100** and **200**, and fills the space between neighboring metal traces **210**. FIG. 1B shows that the copper post (or metal bump) **112** has a width of  $W_1$ , in accordance with some embodiments. FIG. 1B also shows that the metal trace **210** has a width  $W_2$ , in accordance with some embodiments.

In some other embodiments, the ratio of  $L_1/W_1$  is greater than 1. In some embodiments, the ratio of  $L_1/W_1$  is equal to or greater than about 1.2. In some embodiments, the  $L_1$  is in a range from about 10  $\mu\text{m}$  to about 1000  $\mu\text{m}$ . In some embodiments,  $W_1$  is in a range from about 10  $\mu\text{m}$  to about 700  $\mu\text{m}$ . In some embodiments,  $W_2$  is in a range from about 10  $\mu\text{m}$  to about 500  $\mu\text{m}$ . The structure as shown in FIGS. 1A and 1B is referred to as being a BOT structure, because solder layer **220** is formed directly on the top surface and sidewalls of metal trace **210**, and not on a metal pad that has a width significantly greater than width  $W_2$  of metal trace **210**. In some embodiments, the ratio of  $W_1/W_2$  is in a range from about 0.25 to about 1.

FIG. 2A shows a top view of a BOT region **200**, in accordance with some embodiments. FIG. 2A shows a number of metal bumps **201-208** over metal traces **211-218**. The metal traces provide the function of interconnection and connects metal bumps to one another. For example, metal trace **211** connects metal bump **201** and metal bump **202**, in accordance with some embodiments. Metal bumps **201-208** include copper post **112**, UBM layer **110** and solder layer **220** described above.

FIG. 2B shows a cross-sectional view of the BOT region **200** cut along A-A line, in accordance with some embodiments. FIG. 2B shows that metal bumps **201**, **203**, and **205** are placed on metal traces **211**, **213**, and **215**. FIG. 2B also shows cross-sections of metal traces **212** and **214**. Cross sections of metal bumps **201**, **203**, and **205** show a UBM layer **110**, copper posts **112** with solder layer **220**. The solder layer **220** wrap around the exposed surfaces of metal traces **211**, **213** and **215** after reflow. FIG. 2B also shows that the solder layer **220** between copper post **112** of metal bump **201** protrudes beyond surface **231** of copper post **112** with a distance " $D_1$ ". As mentioned above, the reflowed solder of the solder layer

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**220** may also move along surfaces **113** of copper post **112** and cover portions or all of surfaces **113**. Due to the pressure exerted by the work piece **100** on work piece **200**, the surface **221** of solder layer **220** extends beyond the surface **113** of the copper post with a maximum distance of " $D_1$ ." Larger  $D_1$  reduces the distance  $D_2$  between the surface **113** and the neighboring metal trace surface **232** and increases the risk of shorting between metal traces **211** and **212**. In addition,  $D_2$  may be shortened by mis-alignment or by alignment error. With shrinking feature sizes and pitches, minimizing  $D_1$  is important to improve yield. In some embodiments,  $D_2$ , the minimum distance between a bump and a neighboring metal trace, is specified to be equal to or greater than about 0.1  $\mu\text{m}$  to avoid shorting. In some embodiments, the distance between the edge of copper post **112** to a closest edge of a metal trace **212**, or  $D_1+D_2$ , is in a range is equal to or greater than about 1  $\mu\text{m}$ . In some other embodiments, the distance is equal to or greater than about 5  $\mu\text{m}$ .

FIG. 3A shows a cross-sectional view of metal bump **201** before it is coupled to metal trace **211** and before solder reflow, in accordance with some embodiments. FIG. 3A shows that metal bump **201** includes a copper post **112** and a solder layer **220**. There is an optional capping layer **126** between the copper post **112** and the solder layer **220**. The cap layer **126** could act as a barrier layer to prevent copper in the Cu pillar **125** from diffusing into a bonding material, such as solder alloy, that is used to bond the substrate **101** to external features.

The solder layer **220** and copper post **112** may be formed by plating over the UBM layer **110**, in accordance with some embodiments. Prior to the solder reflow, the solder layer **220** and copper post **112** share the same surfaces **113**. FIG. 3B shows a top view of metal bump **201** of FIGS. 2A and 2B before bonding and reflow, in accordance with some embodiments. FIG. 3B shows the outline **310** of copper post **112**. Outline **310** is also the outline for UBM layer **110**. The copper post **112** shown in FIG. 3B is in the shape of a race track with two hemispheres (M sections) coupled to a rectangle (N section). The diameter of the two hemispheres  $W_1$  is the same as the width of the rectangle, which is also shown in FIG. 1B. The total length of the metal bump **201** is  $L_1$ , as shown in FIG. 1A, and the length of the rectangle is  $L_R$ . Although the example in FIG. 3B is in the shape of a race track, other elongated shapes, such as oval shape, etc. are also applicable.

After reflow and under the pressure of being pressed against metal trace **211**, solder layer **220** tends to protrude the most near the center region of the rectangle (N section). This could be due to less surface tension on the side walls of the center region (N section), in comparison to the edge sections (M sections).

As described above, the protrusion of the solder layer **220** (with a maximum protruding distance  $D_1$ ) increases the risk of shorting. FIG. 3C shows a cross-sectional view of a BOT structure, in accordance with some embodiments. FIG. 3C shows that the solder layer **220** of a metal bump **201**\* making contact with a neighboring metal trace **212**\* due to solder extrusion and some alignment error, which is expected due to process variation. As a result, it is desirable to reduce the protruding distance  $D_1$  to reduce of risk of shorting between metal bump **201**, metal trace **211**, and metal trace **212**.

FIG. 4A shows a top view of a metal bump **400**, in accordance with some embodiments. The metal bump is similar to metal bumps **201** described above. FIG. 4A shows an outline **401** of outer boundary of the UBM layer **100**, which also significantly match the outer boundaries of copper post **112** and solder layer **220** before solder reflow. FIG. 4A shows that in order to reduce solder protrusion to reduce the shortest

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distance between the metal bump, such as metal bump **201**, and a neighboring metal trace, such as metal trace **212**, the width of the rectangular section (N section) of the metal bump is reduced from  $W_1$  to  $W_4$ . Each side of the rectangular section is reduced by a width of  $W_3$ . FIG. 4B shows a side view of metal bump **400**, in accordance with some embodiments. Metal bump **400** includes a solder layer **220**, a copper post **112** and an UBM layer **110**, in accordance with some embodiments. Alternatively, metal bump **400** could refer only to the copper post **112** or the copper post **112** with the UBM layer **110**. The height of the solder layer **220** is  $H_1$  and the height of the copper post is  $H_2$ . The height of the UBM layer is  $H_3$ . In some embodiments,  $H_1$  is in a range from about 10  $\mu\text{m}$  to about 50  $\mu\text{m}$ . In some embodiments,  $H_2$  is in a range from about 10  $\mu\text{m}$  to about 70  $\mu\text{m}$ . In some embodiments,  $H_3$  is in a range from about 3  $\mu\text{m}$  to about 15  $\mu\text{m}$ .

As mentioned above, solder layer **220** tends to protrude in the middle section (or N section). By reducing the width of the middle section, the reflowed solder will fill the recess space created by the reduced width of the middle section (or rectangular section N). As a result, the risk of shorting due to protruding solder material can be reduced and yield can be improved. Such reduction to reduce shorting and to improve yield is important for advanced packaging. In some embodiments, the recess region is region R, which is shown in FIG. 4C. FIG. 4A shows that there are two recess regions R for metal bump **400**. Recess region R includes recess region A of the solder layer **220**, recess region B of copper post **112**, and recess region C of the UBM layer **110**, as shown in FIG. 3C in accordance with some embodiments. Equation (1) shows the volume of region R, in accordance with some embodiments.

$$R_{\text{volume}} = W_3 \times L_R \times (H_1 + H_2 + H_3) \quad (1)$$

Although reducing  $W_1$  could reduce the risk of shorting,  $W_1$  cannot be reduced too much to prevent insufficient coverage of solder on the metal trace underneath. In addition, small  $W_1$  would lead to small UBM area, which could increase the stress at the interface **118** (as shown in FIGS. 1A and 1B) next to IMDs **108** and could result in interfacial delamination. Such interfacial delamination is a reliability concern and can affect yield. In some embodiments, the maximum width of the recess region  $W_3$  is in a range from about 1  $\mu\text{m}$  to about 30  $\mu\text{m}$ . In some embodiments, the ratio of  $W_3$  to  $W_1$  is in a range from about 0.02 to about 0.5. In some embodiments, the volume ratio of recess regions R to the solder layer **220** of the metal bump **400** is greater than or equal to about 0.01, which means that the recess regions R for metal bump **400** is equal to or greater than about 1% of the volume of the solder layer **220**. In some other embodiments, the volume ratio of recess regions R to the solder layer **220** of the metal bump **400** is equal to or less than about 0.1. In some embodiments, a ratio of the surface areas (or cross-sectional areas) of recess regions R, as viewed in FIG. 4A, to the surface area (or cross-sectional area) of bump **400** is equal to or greater than about 0.01. In some other embodiments, a ratio of the surface areas (or cross-sectional areas) of recess regions R, as viewed in FIG. 4A, to the surface area (or cross-sectional area) of bump **400** is equal to or less than about 0.1.

Other shapes of recess regions combined with various profiles of metal bumps may also be used to reduce solder metal protrusion. FIG. 4D shows a top view of a metal bump **400'**, in accordance with some embodiments. Metal bump **400'** is similar to metal bump **400**. The corners **402** of regions R of FIGS. 4A, 4B, and 4C are straight (or 90°). The corners **403** of the recess region R' of FIG. 4D is has an angle  $\alpha$ . Angle  $\alpha$  may be equal to or greater than 90°. A greater than 90° corner angle,  $\alpha$ , may have less stress than a straight corner. However,

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angle  $\alpha$  may be designed with an angle less than 90°, in accordance with some embodiments. In some embodiments, the M sections (or end sections) of metal bump **400** do not need to be in hemispherical shape. Other shapes are also possible. Further, the recess regions do not need to be formed by straight walls. FIG. 4E shows a metal bump **400\*** with the recess regions having curved side walls, in accordance with some embodiments. Other shapes and curvatures of sidewalls of recess regions are also possible.

The metal bumps described above without the recess regions have a cross section in the shape of a race track. Bumps with other shapes of cross sections may also be used. For example, the shape of a cross section may be an oval shape. The top views of metal bumps **400** may be in any elongated shapes, including a rectangle with rounded corners. Recess region(s) may be formed in such bumps to allow solder layers to fill (fully or partially) in the recess region(s) after reflow to reduce the risk of shorting.

The embodiments of bump and bump-on-trace (BOT) structures provide bumps with recess regions for reflowed solder to fill. The recess regions are placed in areas of the bumps where reflow solder is most likely to protrude. The recess regions reduce the risk of bump to trace shorting. As a result, yield can be improved.

FIG. 5A is a top view of a bump structure **500** having a single side recess in accordance with some embodiments. Bump structure **500** is similar to bump structure **400** (FIG. 4A) except that bump structure **500** includes a recess on a single side of the bump structure. Bump structure **500** has a general race track shape. Bump structure **500** includes a recess **510** in one side. A side **520** of bump structure **500** opposite recess **510** is substantially straight. Ends **530** of bump structure **500** connect side **520** to the side having recess **510**. Bump structure **500** has an overall width "a" and an overall length "b". Recess **510** has a first length "c" closest to an outer surface of bump structure **500**. Recess **510** has a second length "d" closest to side **520**. A depth "e" of recess **510** is a distance between the outer surface of bump structure **500** and a point of the recess closest to side **520**.

Bump structure **500** is usable for connecting one die to another in a package. Bump structure **500** includes a conductive material. In some embodiments, the conductive material is copper, aluminum, tungsten, or another suitable conductive material. Bump structure **500** connects one die to another using a reflowed solder layer or a reflowed solder ball. During a reflow process, liquefied solder flows into recess **510**. In comparison with bump structures which do not include recess **510**, bump structure **500** is able to achieve a smaller pitch between adjacent bump structures with reduced risk of bridging between solder material of the adjacent bump structures. In some embodiments, bump structure **500** is part of a bump on trace (BOT) structure. In some embodiments, bump structure **500** is configured to connect to another bump structure. In some embodiments, the other bump structure includes at least one recessed side. In some embodiments, the other bump structure includes no recessed sides.

Ends **530** of bump structure **500** are continuous curves. In some embodiments, ends **530** are straight edges with rounded corners, such that a general shape of bump structure **500** is a rectangle having rounded corners as seen in FIG. 5B. In some embodiments, ends **530** have a different shape, such as a triangular (FIG. 5C), a polygon (FIG. 5D), a discontinuous curve (FIG. 5E) or another suitable shape. Ends **530** have a same shape. In some embodiments, one end **530** has a different shape from the other end **530** (FIG. 5F).

Bump structure **500** is usable for a 16 nanometer (nm) technology chip. In some embodiments, bump structure **500**

is usable for a 28 nm technology chip. In some embodiments, bump structure 500 is usable for a 20 nm technology chip. In some embodiments, bump structure 500 is sized for a technology node other than 16 nm, 20 nm or 28 nm. In some embodiments, overall width "a" ranges from about 10 microns ( $\mu\text{m}$ ) to about 200  $\mu\text{m}$ . In some embodiments, overall width "a" ranges from about 25  $\mu\text{m}$  to about 50  $\mu\text{m}$ . If the overall width of bump structure 500 is too small, an electrical resistance of bump structure 500 increases and negatively impacts performance of a die connected to the bump structure; or a risk of the bump structure breaking during a packaging process increases. In addition, a risk of an open connection during a packaging operation due to misalignment increases if the overall width is too small. If the overall width of bump structure 500 is too great, a risk of bridging of solder materials of adjacent bump structures is increased. In some embodiments, overall length "b" ranges from about 20  $\mu\text{m}$  to about 400  $\mu\text{m}$ . In some embodiments, overall length "b" ranges from about 50  $\mu\text{m}$  to about 80  $\mu\text{m}$ . If the overall length of bump structure 500 is too small, the electrical resistance of the bump structure increases and adversely impacts performance of a device connected to the bump structure, in some instances. In addition, a mechanical strength of bump structure 500 is reduced and a risk of breaking during a packaging process increases if the overall length of the bump structure is too small. A risk of misalignment causing an open connection also increases if the overall length of bump structure 500 is too small. If the overall length of bump structure 500 is too large, a risk of bridging between solder materials of adjacent bump structures increases. In some embodiments, a ratio of overall width "a" to overall length "b" ranges from about 0.5 to about 1.0. If the ratio of overall width "a" to overall length "b" is too small, a mechanical strength of bump structure 500 is adversely impacted, in some instances. If the ratio of overall width "a" to overall length "b" is too great, a size of bump structure 500 is increased without a significant increase in performance and functionality, in some instances.

A surface of recess 510 closest to side 520 is parallel to side 520. In some embodiments, the surface of recess 510 closest to side 520 is angled with respect to side 520 (FIG. 5G). In some embodiments, the surface of recess 510 closest to side 520 is curved (FIG. 5H). In some embodiments, the curve is convex. In some embodiments, the curve is concave. In some embodiments, the second length "d" is less than or equal to about 30  $\mu\text{m}$ . In some embodiments, the second length "d" is less than or equal to about 15  $\mu\text{m}$ . In some embodiments, second length "d" is equal to 0 (FIGS. 5G and 5H). In some embodiments, a ratio of the second length "d" to the overall length "b" is less than or equal to about 0.3. In some embodiments, the ratio of the second length "d" to the overall length "b" is less than or equal to about 0.15. The second length is substantially zero when the surface closest to side 520 is curved or sidewalls of recess 510 intersect. If second length "d" or the ratio between the second length and the overall length "b" is too large, the electrical resistance of bump structure 500 increases and negatively impacts performance of a die connected to the bump structure; or a risk of the bump structure breaking during a packaging process increases, in some instances. In addition, a risk of an open connection during a packaging operation due to misalignment increases if second length "d" or the ratio between the second length and the overall length "b" is too large.

First length "c" of recess 510 provides an opening for solder material to flow into the recess during a reflow process. In some embodiments, first length "c" ranges from about 5  $\mu\text{m}$  to about 50  $\mu\text{m}$ . In some embodiments, first length "c" ranges from about 8  $\mu\text{m}$  to about 15  $\mu\text{m}$ . In some embodi-

ments, first length "c" is substantially equal to second length "d" (FIG. 5I). In some embodiments, a ratio between first length "c" and overall length "b" ranges from about 0.3 to about 0.5. If first length "c" is too large or the ratio between first length "c" and overall length "b" is too great, the electrical resistance of bump structure 500 negatively impacts performance of a die connected to the bump structure, in some instances. Additionally, a risk of bump structure 500 breaking during a packaging process increases or an open connection during a packaging operation due to misalignment increases if first length "c" is too large or the ratio between first length "c" and overall length "b" is too great. If first length "c" is too small or the ratio between first length "c" and overall length "b" is too small, a size of recess 510 is not sufficient to reduce the risk of bridging between adjacent bump structures, in some instances.

Depth "e" of recess 510 provides a volume to receive solder material during a reflow process. In some embodiments, depth "e" ranges from about 0.5  $\mu\text{m}$  to about 15  $\mu\text{m}$ . In some embodiments, depth "e" ranges from about 1  $\mu\text{m}$  to about 15  $\mu\text{m}$ . In some embodiments, a ratio of depth "e" to overall width "a" ranges from about 0.05 to about 0.2. If depth "e" is too large or the ratio between depth "e" and overall width "a" is too great, the electrical resistance of bump structure 500 negatively impacts performance of a die connected to the bump structure, in some instances. Additionally, a risk of bump structure 500 breaking during a packaging process increases or an open connection during a packaging operation due to misalignment increases if depth "e" is too large or the ratio between depth "e" and overall width "a" is too great. If depth "e" is too small or the ratio between depth "e" and overall width "a" is too small, the size of recess 510 is not sufficient to reduce the risk of bridging between adjacent bump structures, in some instances.

As a pitch between bump structures decreases, an overall size of the bump structures is reduced. For example, a 28 nm technology node chip includes a bump pitch of about 100  $\mu\text{m}$  to about 160  $\mu\text{m}$ , in some instances. For a chip which is about 10 mm $\times$ 10 mm, the number of bump structures is approximately 1000 bump structures to connect the chip to another structure. In contrast, a 16 nm technology node chip includes a bump pitch of about 80  $\mu\text{m}$  to about 120  $\mu\text{m}$ , in some embodiments. The 16 nm technology node chip will have 3-4 times the number of bump structures for a 10 mm $\times$ 10 mm chip in comparison with the 28 nm technology node chip. In some embodiments, a 10 nm technology chip includes a bump pitch of about 40  $\mu\text{m}$  to about 100  $\mu\text{m}$ . The 10 nm technology chip will have even more bump structures for a 10 mm $\times$ 10 mm chip than a 16 nm technology node chip. Due to the increased number of bump structures on a chip as technology nodes decrease, recessing both sides of the bump structures has a greater overall impact in an ability of a chip including the recessed bump structures to maintain functionality when packaged with another structure due to increased resistance. In addition, mechanical strength of a connection point between a bump structure having a single recess side (FIG. 5A) and a die is greater than a connection point between a bump structure having recesses on both sides (FIG. 4A) and a die. By recessing a single side of bump structures 500, the increased resistance and reduced mechanical strength of the bump structure resulting from the recess is reduced in comparison with a bump structure which is recessed on both sides of the bump structure.

FIG. 6 is a top view of a bump structure 600 having a single side recess in accordance with some embodiments. Bump structure 600 includes a recess 610 offset from a center of a length of the bump structure. In some embodiments, an offset

distance  $z$  from a center of recess **610** to the center of the length of bump structure **600** is less than or equal to about  $7\text{ }\mu\text{m}$ . In some embodiments, a ratio of offset  $z$  to an overall length of bump structure **600** is less than or equal to about 0.15. If offset  $z$  is too large or the ratio between offset  $z$  and the overall length of bump structure **600** is too great, a risk of an open connection during a packaging operation due to misalignment increases, in some instances.

FIG. 7 is a top view of an array **700** of bump structures **750** having a single side recess on a die in accordance with some embodiments. Array **700** includes a pitch  $P$  between adjacent bump structure **750**. Center lines **710a** and **710b** divide array **700** into four substantially equal quadrants. Each bump structure **750** of array **700** includes a single recess, similar to bump structure **500** (FIG. 5). A line **710c** extends from a center of array **700** to a corner of the array. In some embodiments, bump structures **750** which are in a core region or a corner region of array **700** are angled so that a longitudinal axis of the bump structure is substantially parallel to line **710c**.

A side of bump structures **750** including a recess is oriented toward a closest center line of center line **710a** and center line **710b**. That is, a bump structure, such as bump structure **750a**, which is located closer to center line **710a** than center line **710b** includes a recess in the side of the bump structure facing center line **710a**. Conversely, a bump structure, such as bump structure **750b**, located closer to center line **710b** than center line **710a** includes a recess in the side of the bump structure facing center line **710b**. In some embodiments, a bump structure, such as bump structure **750c**, which is equidistant from center line **710a** and center line **710b** includes a recess in the side of the bump structure facing center line **710a**. In some embodiments, a first bump structure **750** which is equidistant from center line **710a** and center line **710b** has a recess in the side of the first bump structure facing center line **710a** and a second bump structure **750** which is equidistant from center line **710a** and center line **710b** has a recess in the side of the second bump structure facing center line **710b**. In some embodiments, pitch  $P$  between adjacent bump structures **750** ranges from about  $40\text{ }\mu\text{m}$  to about  $200\text{ }\mu\text{m}$ .

Bump structures **750** are bonded to another die using a solder reflow process. In some embodiments, bump structures **750** are part of an active die, a passive die, an interposer, or another suitable connection structure. The recess of bump structures **750** is oriented toward the closest center line **710a** or **710b** in order to capture reflowed solder material during a packaging process. During the solder reflow process, a die being bonded to bump structures **750** is heated. In some embodiments, the die is an active die, a passive die, an interposer or another suitable connection structure. When the die cools the die shrinks. A magnitude of the shrinkage of the die is based on a coefficient of thermal expansion of a material of the die and an overall size of the die. This shrinking causes edges of the bonded die to move inwardly in a plane parallel to array **700** toward center line **710a** and center line **710b**. The movement of the edges of the die pulls solder material, which is still cooling from the reflow process toward, center line **710a** and center line **710b**. For example, referring to FIG. 3C, a center line of a die having trace **211\*** and trace **212\*** is located to a right side of trace **212\***. As the die shrinks toward a center of the die following a reflow process solder **220** is pulled toward the center of the die. In structures which do not include the recess of bump structures **750**, the pulling of the solder material during shrinkage of the die is most likely to cause bridging in a direction toward the center line **710a** and

center line **710b**. By including the recesses of bump structures **750** oriented toward a closest center line of center line **710a** or center line **710b**, the risk of bridging in the direction of shrinkage is reduced in comparison with structures that do not include the recess. In some embodiments, a depth, e.g., depth “e” (FIG. 5A), of the recess of bump structures **750** is determined based on the coefficient of thermal expansion of the die bonded to bump structures **750** or a size of the die bonded to bump structures **750**. In some embodiments, as the coefficient of thermal expansion of the die bonded to bump structures **750** increases the depth of the recesses of bump structures **750** increases. In some embodiments, as the size of the die bonded to bump structures **750** increases, the depth of the recesses of bump structures **750** increases.

FIG. 8 is a top view of a portion of an array **800** of bump structures having a single side recess on a die in accordance with some embodiments. FIG. 8 includes half of array **800**, i.e., the half of array **800** below a center line **810a**. In comparison with array **700** (FIG. 7), array **800** includes at least one bump structure which does not include a recess. Array **800** includes a core region **820** having bump structures. Bump structures in core region **820** include non-recessed sides. In some embodiments, at least one bump structure in core region **820** includes a recess. The bump structures of core region **820** have a longitudinal axis at an angle with respect to center line **810a** and center line **810b**. Array **800** also includes a corner region **830** having bump structures. Bump structures in corner region **830** include non-recessed sides, similar to bump structures in core region **820**. In some embodiments, at least one bump structure in corner region **830** includes a recess. The bump structures in corner region **830** have a longitudinal axis oriented at an angle to center line **810a** and center line **810b**. A central peripheral region **840** of array **800** also includes bump structures. Bump structures of central peripheral region **840** include non-recessed sides. In some embodiments, at least one bump structure in central peripheral region **840** includes a recess. The bump structures in central peripheral region **840** have a longitudinal axis substantially parallel to a closest center line of center line **810a** or center line **810b**. In some embodiments, an arrangement of bump structures in corner region **830** and core region **820** has a layout based on the bump arrangement described in U.S. Pat. No. 8,598,691, which is incorporated herein by reference in its entirety. Array **800** also includes a recess peripheral region **850** including bump structures. Each bump structure in recess peripheral region **850** includes a recess oriented toward a closest center line of center line **810a** or center line **810b**. Recess peripheral region **850** is located at an edge of array **800** between central peripheral region **840** and corner region **830**. The bump structures of recess peripheral region **850** have a longitudinal axis substantially parallel to the closest center line of center line **810a** or center line **810b**.

As discussed above, recessed bump structures have increased electrical resistance in comparison with a bump structure having non-recessed sides. The recessed bump structure also has a lower mechanical strength than non-recess bump structures. By concentrating recessed bump structures in regions of array **800** where a bridging risk is highest, the above drawbacks of recessing the sides of the bump structures are mitigated in other portions of array **800**. Recess peripheral region **850** is a location of highest bridging risk of array **800** because the edge of the die bonded to the bump structures of array **800** experiences a largest magnitude of shrinkage following a reflow process.

Array **800** includes recess peripheral region **850** having a single row of bump structures. In some embodiments, recess peripheral region **850** includes multiple rows of bump struc-

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tures. In some embodiments, array 800 includes a single recess peripheral region 850. In some embodiments, the single recess peripheral region 850 includes a single recessed bump structure. In some embodiments, the single recessed bump structure is adjacent to a corner region 830 of array 800.

In some embodiments, as the coefficient of thermal expansion of the die bonded to array 800 increases, a size of recess peripheral region 850 increases. In some embodiments, as the size of the die bonded to array 800 increases, the size of recess peripheral region 850 increases. In some embodiments, the size of recess peripheral region 850 is determined based on empirical evidence from previous package structures.

FIG. 9 is a top view of a die 900 having bump structures having a single side recess in accordance with some embodiments. Die 900 includes core region 920 similar to core region 820 (FIG. 8). Die 900 further includes corner region 930 similar to corner region 830. Die 900 further includes recess peripheral region 950 similar to recess peripheral region 850. In some embodiments, die 900 also includes a central peripheral region similar to central peripheral region 840.

A first corner region extending parallel to center line 910a has a length  $\times 1$  parallel to center line 910a. In some embodiment, a ratio of length  $\times 1$  to an overall length L of die 900 parallel to center line 910a ranges from about 0.02 to about 0.1. If the ratio of length  $\times 1$  to the overall length of die 900 is too great, a risk of bridging of bump structures within the first corner region increases, in some instances. If the ratio of length  $\times 1$  to the overall length of die 900 is too small, a mechanical structure of the bump structures in the first corner region is needlessly reduced or the electrical resistance of the bump structures in the first corner region is needlessly increased, in some instances.

A first recess peripheral region extending parallel to center line 910a has a length  $y_1$  parallel to center line 910a. In some embodiment, a ratio of length  $y_1$  to an overall length L of die 900 parallel to center line 910a ranges from about 0.2 to about 0.3. If the ratio of length  $y_1$  to the overall length of die 900 is too great, a mechanical structure of the bump structures in the first recess peripheral region is needlessly reduced or the electrical resistance of the bump structures in the first recess peripheral region is needlessly increased, in some instances. If the ratio of length  $y_1$  to the overall length of die 900 is too small, a risk of bridging of bump structures within the first corner region increases, in some instances.

A second corner region extending parallel to center line 910a has a length  $x_2$  parallel to center line 910a. In some embodiment, a ratio of length  $x_2$  to an overall length of die 900 parallel to center line 910a ranges from about 0.02 to about 0.1. If the ratio of length  $x_2$  to the overall length L of die 900 is too great, a risk of bridging of bump structures within the first corner region increases, in some instances. If the ratio of length  $x_2$  to the overall length of die 900 is too small, a mechanical structure of the bump structures in the first corner region is needlessly reduced or the electrical resistance of the bump structures in the first corner region is needlessly increased, in some instances. In some embodiments, length  $x_2$  is equal to length  $x_1$ . In some embodiments, length  $x_2$  is different from length  $x_1$ . In some embodiments, a magnitude of length  $x_1$  or length  $x_2$  is determined based on empirical information, a coefficient of thermal expansion of a die bonded to die 900, or a size of the die bonded to die 900.

A second recess peripheral region extending parallel to center line 910a has a length  $y_2$  parallel to center line 910a. In some embodiment, a ratio of length  $y_2$  to an overall length L of die 900 parallel to center line 910a ranges from about 0.2 to about 0.3. If the ratio of length  $y_2$  to the overall length of die 900 is too great, a mechanical structure of the bump structures

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in the first recess peripheral region is needlessly reduced or the electrical resistance of the bump structures in the first recess peripheral region is needlessly increased, in some instances. If the ratio of length  $y_2$  to the overall length of die 900 is too small, a risk of bridging of bump structures within the first corner region increases, in some instances. In some embodiments, length  $y_2$  is equal to length  $y_1$ . In some embodiments, length  $y_2$  is different from length  $y_1$ . In some embodiments, a magnitude of length  $y_1$  or length  $y_2$  is determined based on empirical information, a coefficient of thermal expansion of a die bonded to die 900, or a size of the die bonded to die 900.

A third corner region extending parallel to center line 910b has a length  $i_1$  parallel to center line 910b. In some embodiment, a ratio of length  $i_1$  to an overall length K of die 900 parallel to center line 910b ranges from about 0.02 to about 0.1. If the ratio of length  $i_1$  to the overall length of die 900 is too great, a risk of bridging of bump structures within the first corner region increases, in some instances. If the ratio of length  $i_1$  to the overall length of die 900 is too small, a mechanical structure of the bump structures in the first corner region is needlessly reduced or the electrical resistance of the bump structures in the first corner region is needlessly increased, in some instances.

A third recess peripheral region extending parallel to center line 910b has a length  $j_1$  parallel to center line 910b. In some embodiment, a ratio of length  $j_1$  to an overall length K of die 900 parallel to center line 910b ranges from about 0.2 to about 0.3. If the ratio of length  $j_1$  to the overall length of die 900 is too great, a mechanical structure of the bump structures in the first recess peripheral region is needlessly reduced or the electrical resistance of the bump structures in the first recess peripheral region is needlessly increased, in some instances. If the ratio of length  $j_1$  to the overall length of die 900 is too small, a risk of bridging of bump structures within the first corner region increases, in some instances.

A fourth corner region extending parallel to center line 910b has a length  $i_2$  parallel to center line 910b. In some embodiment, a ratio of length  $i_2$  to an overall length K of die 900 parallel to center line 910b ranges from about 0.02 to about 0.1. If the ratio of length  $i_2$  to the overall length of die 900 is too great, a risk of bridging of bump structures within the first corner region increases, in some instances. If the ratio of length  $i_2$  to the overall length of die 900 is too small, a mechanical structure of the bump structures in the first corner region is needlessly reduced or the electrical resistance of the bump structures in the first corner region is needlessly increased, in some instances. In some embodiments, length  $i_2$  is equal to at least one of length  $x_1$ , length  $x_2$  or length  $i_1$ . In some embodiments, length  $x_2$  is different from at least one of length  $x_1$ , length  $x_2$  or length  $i_1$ . In some embodiments, a magnitude of length  $i_1$  or length  $i_2$  is determined based on empirical information, a coefficient of thermal expansion of a die bonded to die 900, or a size of the die bonded to die 900.

A fourth recess peripheral region extending parallel to center line 910b has a length  $j_2$  parallel to center line 910b. In some embodiment, a ratio of length  $j_2$  to an overall length K of die 900 parallel to center line 910b ranges from about 0.2 to about 0.3. If the ratio of length  $j_2$  to the overall length of die 900 is too great, a mechanical structure of the bump structures in the first recess peripheral region is needlessly reduced or the electrical resistance of the bump structures in the first recess peripheral region is needlessly increased, in some instances. If the ratio of length  $j_2$  to the overall length of die 900 is too small, a risk of bridging of bump structures within the first corner region increases, in some instances. In some embodiments, length  $j_2$  is equal to at least one of length  $y_1$ ,



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length  $y_2$  or length  $j_1$ . In some embodiments, length  $j_2$  is different from at least one of length  $y_1$ , length  $y_2$  or length  $j_1$ . In some embodiments, a magnitude of length  $j_1$  or length  $j_2$  is determined based on empirical information, a coefficient of thermal expansion of a die bonded to die 900, or a size of the die bonded to die 900.

FIG. 10A is a top view of a BOT region 1000 in accordance with some embodiments. BOT region 1000 is similar to workpiece 200 and similar elements have a same reference number increased by 200. In comparison with workpiece 200 BOT region 1000 includes bump structures 1001-1008 including a recess 1050. Each recess 1050 is facing toward a center of a die including BOT region 1000, i.e., to a right side of FIG. 10A. Recess 1050 is configured to receive solder which is reflowed during a bonding of bump structures 1001-1008 to corresponding traces 1011-1018. Bump structures 1001-1008 are wider than traces 1011-1018. FIG. 10A includes each trace 1011-1018 fully landed on by a corresponding bump structure 1001-1008. In some embodiments, at least one trace 1011-1018 is only partially landed on by a corresponding bump structure 1001-1008. Traces 1011-1018 are conductive lines. In some embodiments, traces 1011-1018 include copper, aluminum, tungsten, or another suitable conductive material.

FIG. 10B is a cross-sectional view of BOT region 1000 taken along line B-B in accordance with some embodiments. BOT region 1000 includes a first work piece 100' bonded to a second work piece 200'. Second work piece 200' includes traces 1011-1018. Traces 1011-1018 are electrically connected to active elements or passive elements within second work piece 200'. First work piece 100' includes bump structures 1001-1008. Bump structures 1001-1008 are electrically connected to active elements or passive elements within the first work piece 100'.

Bump structure 1001-1008 includes a conductive post 1022, a solder material 1024 and a UBM layer 1026. During a bonding process, solder material 1024 is reflowed in order to bond with a corresponding trace 1011-1018. When solder material 1024 is reflowed a portion of the reflowed solder material flows into recess 1050. The portion of solder material 1024 which flows into recess 1050 reduces a total width of the bonded bump structure 1001-1008 in comparison with a bump structure which does not include recess 1050. The reduced width of bump structure 1001-1008 reduces facilitates a reduced pitch between bump structures by reducing a risk of bridging between adjacent bump structures in an array having the reduced pitch. Reducing a pitch between bump structures 1001-1008 facilitates an increased density of connections between first work piece 100' and second work piece 200'.

FIG. 11A is a cross-sectional view of a BOT region 1100 in accordance with some embodiments. BOT region 1110 is similar to BOT region 1000 (FIG. 10B). Same elements have a same reference number increased by 100. In comparison with BOT region 1000, BOT region 1100 does not include first work piece 100'. Conductive post 1122 is able to be bonded to an additional work piece. In some embodiments, the additional work piece includes a work piece including active circuitry, a work piece including passive circuitry, an interposer or another suitable work piece. Recess 1150 is indicated as a dotted line because the recess is located in a plane other than the cross-sectional view of BOT region 1100.

FIG. 11B is a perspective view of a bump structure 1100' in accordance with some embodiments. An overall shape of bump structure 1100' is rectangular and includes flat end faces and rounded corners. Bump structure 1100' also includes a trapezoidal recess. In some embodiments, the overall shape of

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bump structure 1100' is different from a rectangular shape, as indicated in FIGS. 5A-5I. In some embodiments, the recess of bump structure 1100' is different form a trapezoidal shape, as indicated in FIGS. 5A-5I.

One aspect of this description relates to a bump structure. The bump structure includes a first end; and a second end opposite the first end. The bump structure further includes a side connected between the first end and the second end, wherein the side comprises a recess for a reflowed solder material to fill, and the recess defines a first surface adjacent to the first end and a second surface adjacent to the second end.

Another aspect of this description relates to a semiconductor structure. The semiconductor structure includes a plurality of bump structures configured to electrically connect to a separate die. Each bump structure of the plurality of bump structures includes a first end; and a second end opposite the first end. Each bump structure further includes a side connected between the first end and the second end, wherein the side comprises a recess for a reflowed solder material to fill. A recess for a first bump structure of the plurality of bump structures is oriented in a first direction. A recess for a second bump structure of the plurality of bump structures is oriented in a second direction different from the first direction.

Still another aspect of this description relates to a semiconductor structure. The semiconductor structure includes a plurality of bump structures configured to electrically connect to a separate die. Each bump structure of the plurality of bump structures includes a first end; and a second end opposite the first end. Each bump structure further includes a side connected between the first end and the second end, wherein the side comprises a recess for a reflowed solder material to fill. A first end for a first bump structure of the plurality of bump structures is oriented a first direction. A first end for a second bump structure of the plurality of bump structures is oriented a second direction different from the first direction.

Although the embodiments and their advantages have been described in detail, it should be understood that various changes, substitutions and alterations can be made herein without departing from the spirit and scope of the embodiments as defined by the appended claims. Moreover, the scope of the present application is not intended to be limited to the particular embodiments of the process, machine, manufacture, and composition of matter, means, methods and steps described in the specification. As one of ordinary skill in the art will readily appreciate from the disclosure, processes, machines, manufacture, compositions of matter, means, methods, or steps, that perform substantially the same function or achieve substantially the same result as the corresponding embodiments described herein may be utilized according to the disclosure. Accordingly, the appended claims are intended to include within their scope such processes, machines, manufacture, compositions of matter, means, methods, or steps. In addition, each claim constitutes a separate embodiment, and the combination of various claims and embodiments are within the scope of the disclosure.

What is claimed is:

1. A bump structure comprising:

a first end;

a second end opposite the first end;

a side connected between the first end and the second end, wherein the side comprises a recess, and the recess defines a first surface adjacent to the first end and a second surface adjacent to the second end; and

wherein a depth of the recess into the bump structure ranges from about 0.5  $\mu\text{m}$  to about 15  $\mu\text{m}$ .

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2. The bump structure of claim 1, wherein the first surface is substantially planar and the second surface is substantially planar.

3. The bump structure of claim 2, wherein the first surface directly contacts the second surface.

4. The bump structure of claim 2, wherein the recess further defines a third surface connecting the first surface to the second surface.

5. The bump structure of claim 4, wherein the third surface is substantially perpendicular to at least one of the first surface or the second surface.

6. The bump structure of claim 4, wherein the third surface is a curved surface.

7. The bump structure of claim 4, wherein a length of the third surface is equal to or less than about 30 microns ( $\mu\text{m}$ ).

8. The bump structure of claim 1, wherein a shape of the first end is different from a shape of the second end.

9. The bump structure of claim 1, wherein a maximum distance between the first surface and the second surface ranges from about 8  $\mu\text{m}$  to about 15  $\mu\text{m}$ .

10. The bump structure of claim 1, further comprising:

a solder layer;

a copper post layer arranged onto the solder layer, and an under-bump metallurgy (UBM) layer arranged onto the copper post layer, wherein the recess is arranged within sidewalls of the solder layer, the copper post layer, and the UBM layer.

11. A semiconductor structure comprising:

a plurality of bump structures configured to electrically connect to a separate die, wherein each bump structure of the plurality of bump structures comprises:

a first end;

a second end opposite the first end; and

a side connected between the first end and the second end, wherein the side comprises a recess,

wherein a recess for a first bump structure of the plurality of bump structures is oriented in a first direction, and a recess for a second bump structure of the plurality of bump structures is oriented in a second direction different from the first direction.

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12. The semiconductor structure of claim 11, wherein the first direction is toward a closest center line of the semiconductor structure with respect to the first bump structure.

13. The semiconductor structure of claim 12, wherein the second direction is toward the closest center line of the semiconductor structure with respect to the first bump structure.

14. The semiconductor structure of claim 11, wherein the first direction is angled with respect to the second direction.

15. The semiconductor structure of claim 11, wherein the first direction is perpendicular with respect to the second direction.

16. The semiconductor structure of claim 11, wherein a recess for a third bump structure of the plurality of bump structures is oriented in a third direction different from the first direction and from the second direction.

17. The semiconductor structure of claim 11, further comprising a plurality of non-recessed bump structures configured to electrically connect to the separate die.

18. The semiconductor structure of claim 17, wherein the first bump structure is adjacent to at least one non-recessed bump structure of the plurality of non-recessed bump structures.

19. A semiconductor structure comprising:

a plurality of bump structures configured to electrically connect to a separate die, wherein each bump structure of the plurality of bump structures comprises:

a first end;

a second end opposite the first end; and

a side connected between the first end and the second end, wherein the side comprises a recess,

wherein a first end for a first bump structure of the plurality of bump structures is oriented a first direction, and a first end for a second bump structure of the plurality of bump structures is oriented a second direction different from the first direction.

20. The semiconductor structure of claim 19, wherein the first direction is perpendicular with respect to the second direction.

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